

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants: Bai et al.

Examiner: Raymond, Brittany L

Serial No: 10/802,150

Group Art Unit: 1756

Filed: March 17, 2004

Docket: 8021-215 (SS-19582-US)

**FOR: ETCHING PROCESS INCLUDING PLASMA PRETREATMENT FOR  
GENERATING FLUORINE-FREE CARBON-CONTAINING POLYMER ON A  
PHOTORESIST PATTERN**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE TO FINAL OFFICE ACTION**

This response is submitted in response to the Office Action dated February 12,  
2008 in connection with the above-referenced application.